Lecture contents

- P-n junction
 - Current : Shockley model
 - Generation-recombination current
 - High injection

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Currents in p-n junction

First we will use Shockley approximation:

- 1. Low injection = Fermi level do not change in the depletion layer = minority carrier densities << majority carrier densities = majority carrier density equals to doping concentration: $p_n << n_{n0} = N_d$ (in n-region and similar in p-region)
- 2. Non-degenerate = Boltzmann statistics
- 3. Drift-diffusion current (diffusion in quasi-neutral regions)
- 4. Long-base diode: length of the quasi-neutral regions is much larger than the diffusion length of the minority carriers L_n , L_p .
- 5. No generation/recombination in the depletion layer
- 6. Abrupt depletion layer approximation

Let' apply bias and calculate current through the p-n junction

Shockley model: Carrier concentrations and currents (N_d>N_a)



Currents in p-n junction: Shockley theory

Definitions of quasi-Fermi levels:

$$n = n_i \exp\left(\frac{E_{Fn} - E_i}{kT}\right) = N_c \exp\left(\frac{E_{Fn} - E_c}{kT}\right)$$
$$p = n_i \exp\left(\frac{E_i - E_{Fp}}{kT}\right) = N_v \exp\left(\frac{E_v - E_{Fp}}{kT}\right)$$

Potential across the junction:

$$qV_a = E_{Fp} - E_{Fn}$$

Minority carrier concentrations at the edges of the depletion region (will serve as boundary conditions):



Currents in p-n junction

Let's find how minority carriers currents recombine:

Continuity equation for electrons in p-region:

$$\frac{\partial n}{\partial t} = G_n - R_n + \frac{1}{q} \nabla \cdot J_n \qquad \Longrightarrow \qquad 0 = -\frac{n_p - n_{p0}}{\tau_n} + \frac{1}{q} \frac{\partial J_n}{\partial x}$$

And diffusion current (no drift in the quasineutral region):

$$J_n = nq\mu_n \mathcal{E} + qD_n \nabla n \quad \Longrightarrow \quad J_n = qD_n \frac{\partial n}{\partial x}$$

Currents



Currents in p-n junction

Integrating minority carrier concentration

$$\frac{\partial^2 n_p}{\partial x^2} = \frac{n_p - n_{p0}}{D_n \tau_n}$$

with boundary condition

$$n_p(-x_p) = \frac{n_i^2}{N_a} e^{V_a/V_t}$$

$$n_{p}(x) = n_{p0} + n_{p0} \left(e^{V_{a}/V_{t}} - 1 \right) e^{\left(x + x_{p} \right) / \sqrt{D_{n} \tau_{n}}}$$

And the minority electron current using diffusion length:

$$L_n = \sqrt{D_n \tau_n}$$

$$J_n = qD_n \frac{\partial n}{\partial x} = q \frac{D_n n_{p0}}{L_n} \left(e^{V_a/V_t} - 1 \right) e^{\left(x + x_p\right)/L_n}$$

And similar for minority hole current:

$$J_{p} = q \frac{D_{p} p_{n0}}{L_{p}} \left(e^{V_{a}/V_{t}} - 1 \right) e^{-(x-x_{n})/L_{p}}$$

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I-V characteristics of p-n junction: Shockley model

If we can ignore the change of current in the depletion region (no generation/recombination), we can obtain total current as a sum of minority carrier currents at respective edges of depletion region:

Combining:

With saturation current:

(Mostly determined by low-doped side!)



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Bias and currents in p-n junction



Shockley model and its limitations

Shockley model works for **narrow-bandgap** semiconductors at **low current** densities (e.g. Ge at room temperature) when **depletion region width is much smaller than diffusion length** of minority carriers, and the **device is much longer than the diffusion lengths.**

Also the drift-difusion approximation should be valid \rightarrow low doping level at least from one side

Departures from the ideal equation is due to

- Short base
- Generation-recombination in the depletion region
- Surface effects: leakage currents due to band bending
- Tunneling of carriers between states in bandgap
- Series resistance

I-V characteristics of an ideal diode: semilog plot



I-V characteristics of an ideal diode

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Realistic p-n junction characteristics

I-V characteristics of a Si diode



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Generation-recombination in the depletion region

Generation/recombination in the depletion region violates one of the Shockley approximations (#5)

- <u>Radiative</u> recombination in the depletion region:
 - is almost constant throughout the depletion region
 - Integration of the recombination rate in the depletion region increases the diode current but still has 60mV/dec. slope:

$$0 = \overline{G_n - R_n} + \frac{1}{q} \frac{dJ_n}{dx}$$

B- radiative recombination constant

$$v_{th} \sigma \neq q W n_i^2 (e^{Va/Vt} - 1) v_{th} \sigma$$

 $U_{SHR} = \frac{np - n_i^2}{(p + n_i)\tau_{n0} + (n + n_i)\tau_{n0}}$

$$-\Delta J_n = \Delta J_p = q U_{b-b} W = q W (np - n_i^2) (v_{th} \sigma \neq q W n_i^2 (e^{Va/Vt} - 1) v_{th} \sigma$$

- Trap-assisted generation-recombination : Shockley-Hall-Reed (SHR) processes (with a trap close to intrinsic Fermi level $E_t = E_i$) :
 - If lifetimes are equal, the trap-assisted recombination is the highest for $n = p = n_i e^{V_a/2V_t}$ $U_{SHRmax} = \frac{n_i \left(e^{V_a/2V_t} 1\right)}{2\pi}$
 - The SHR recombination current is obtained by integration of the rate over the depletion region (120 mV/dec. slope): $\Delta J_n = -\Delta J_p = q U_{SHRmax} x' = q x' n_i (e^{Va/2Vt} - 1)/2\tau_0$

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Generation-recombination in the depletion region

• <u>Total diode current</u> with contribution of radiation/recombination:

$$J_{t} = q \left(\frac{D_{n} n_{p0}}{L_{n}} + \frac{D_{p} p_{n0}}{L_{p}} + W n_{i}^{2} v_{th} \sigma \right) \left(e^{V_{a}/V_{t}} - 1 \right) + \frac{q x' n_{i}}{2\tau_{0}} \left(e^{V_{a}/2V_{t}} - 1 \right)$$

• <u>At reverse bias</u> the carrier concentrations in the depletion region are small:

$$np \ll n_i^2$$

• The **generation** of carriers is the dominant process

Dominant term when G-R in depletion region takes place

• The total reverse current will be higher than in Shockley model:

$$J_{reverse} = q \sqrt{\frac{D_p}{\tau_p}} \frac{n_i^2}{N_D} + BWn_i^2 + \frac{qn_ix'}{2\tau_0}$$

High injection (direct bias)

High injection violates one of the Shockley approximations that the majority carriers are determined by thermal equilibrium: $p_n(-x_n) = p_{n0}(-x_n) = N_a$

but they are not. If $n_p(-x_p) \approx p_{p0}(-x_p)$ neutrality should lead to $p_p(-x_p) = p_{p0}(-x_p) + n_p(-x_p)$



Solving quadratic equations:

The current will be (also ignoring recombination in the depletion region):

$$J_n + J_p = q \left(\frac{D_n}{L_n} + \frac{D_p}{L_p}\right) n_i e^{V_a/2V_t}$$
Reduced slope,
120mV/dec.

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Quasi-Fermi levels

Definitions of quasi-Fermi levels:

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$$E_{Fn} = E_i + kT \ln \frac{n}{n_i}$$

Electrostatic potential across the junction:

$$qV_a = E_{Fp} - E_{Fn}$$

Quasi-Fermi level can be related to the driftdiffusion current density:

$$\mu_n n \frac{dE_{Fn}}{dx} = \mu_n n \frac{dE_i}{dx} + kT \frac{\mu_n n}{n} \frac{dn}{dx} = q \mu_n \left(n \mathcal{E} + \frac{kT}{q} \mu_n \frac{dn}{dx} \right) = J_n \quad \Longrightarrow \quad J_n = \mu_n n \frac{dE_{Fn}}{dx}$$

Constant quasi-Fermi level implies that the electrostatic force equals the diffusion force: $q \ \mathcal{E} = -q \ V_1$

$$q \mathcal{E} = -q V_t \frac{d(\ln n)}{dx}$$

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Or

Junction breakdown

Junction breakdown occurs at high reverse bias.

Avalanche multiplication (impact ionization of ٠ electron-hole pairs)



- Tunneling through the junction Zener ٠ breakdown (at high doping concentrations), identical to that of tunneling in a metalsemiconductor junction.
- Thermal: junction temperature increases ٠ leading to increase of saturation current



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